



CRIS 5

Docket No.: 57017.P025

Patent

Inventor(s): MATTHEWS, J.

(inventor(s))

Serial No.: 07/863,791

Filed: APRIL 6, 1992

For: METHOD FOR IMPROVED LITHOGRAPHIC PATTERNING IN A SEMICONDUCTOR

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FABRICATION PROCESS

APR 22 1993

(title)

GROUP 150

THE COMMISSIONER OF PATENTS AND TRADEMARKS  
Washington, D.C. 20231

SIR: Transmitted herewith is an Amendment for the above application.

☐ Small entity status of this application under 37 C.F.R. §§ 1.9 and 1.27 has been established by a verified statement previously submitted.☐ A verified statement to establish small entity status under 37 C.F.R. §§ 1.9 and 1.27 is enclosed.☒ No additional fee is required.

The fee has been calculated as shown below:

(Col. 1)		(Col. 2)		(Col. 3)	SMALL ENTITY		OTHER THAN A SMALL ENTITY	
	Claims Remaining After Amd.		Highest No. Previously Paid For	Present Extra	Rate	Additional Fee	Rate	Additional Fee
Total Claims	*	Minus	**		x10	\$	x20	\$
Indep. Claims	*	Minus	***		x30	\$	x60	\$
<input type="checkbox"/> First Presentation of Multiple Dependent Claim(s)					+100	\$	+200	\$
					Total	\$	Total	\$
					Add. Fee	\$	Add. Fee	\$

\* If the entry in Col. 1 is less than the entry in Col. 2, write "0" in Col. 3.

\*\* If the "Highest No. Previously Paid For" IN THIS SPACE is less than 20, write "20" in this space.

\*\*\* If the "Highest No. Previously Paid For" IN THIS SPACE is less than 3, write "3" in this space.  
The "Highest No. Previously Paid For" (Total or Independent) is the highest number found from the equivalent box in Col. 1 of a prior amendment or the number of claims originally filed.☐ A check in the amount of \$ \_\_\_\_\_ is attached for presentation of additional claim(s).☐ Applicant(s) hereby Petition(s) for an Extension of Time of \_\_\_\_\_ month(s) pursuant to 37 C.F.R. § 1.136(a).☐ A check for \$ \_\_\_\_\_ is attached for processing fees under 37 C.F.R. § 1.17.☐ Please charge my Deposit Account No. 02-2666 the amount of \$ \_\_\_\_\_.**A duplicate copy of this sheet is enclosed.**☒ The Commissioner is hereby authorized to charge payment of the following fees associated

with this communication or credit any overpayment to Deposit Account No. 02-2666

**(a duplicate copy of this sheet is enclosed):**☒ Any additional filing fees required under 37 C.F.R. § 1.16 for presentation of extra claims.☒ Any extension or petition fees under 37 C.F.R. § 1.17.

BLAKELY SOKOLOFF TAYLOR &amp; ZAFMAN

Date: 4/13/93

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I hereby certify that this correspondence is being deposited with the United States Postal Service as First Class mail with sufficient postage in an envelope addressed to the Commissioner of Patents and Trademarks, Washington, D.C. 20231

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Pearl E. Dworkin

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4/13/93

Date

57017.P025



Patent

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

EAP  
05/21/93  
5/a

In re Application of

MATTHEWS, J.

Serial No. 07/863,791

Filing Date: April 6, 1992

For: METHOD FOR IMPROVED  
LITHOGRAPHIC PATTERNING IN A  
SEMICONDUCTOR FABRICATION  
PROCESS

Examiner: Dodson, S.

Art Unit: 1503

Amendment

Box Non-Fee Amendments (Pats)  
Commissioner of Patents and Trademarks  
Washington, D.C. 20231

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Sir:

In response to the Office Action dated March 29, 1993, please enter the following amendment and consider the following remarks:

IN THE SPECIFICATION:

On page 4, line 9, change "radiation" to -- radiation --.

On page 7, line 32, delete ".".

IN THE CLAIMS:

Please cancel claim 13 without prejudice.

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a1

1. (Amended) A method of printing a two-dimensional feature on a substrate, said feature having first and second edges spaced in close proximity to one another, said method comprising the steps of:

- (a) depositing a radiation-sensitive material on said substrate;
- (b) providing a first mask image segment which corresponds to said first edge;
- (c) exposing said first mask image segment with radiation using an imaging tool to produce a first pattern edge gradient, said first pattern edge gradient defining said first edge of said two-dimensional feature in said material;

A